

Application No.:

10/056,154

Confirmation No.:

2279

First-named Inventor:

Fortin, Vincent

Filing Date:

23 January 2002

Group Art Unit:

2823

Examiner:

Lee, Hsien Ming

Attorney Docket No.:

M-12524 US

Title:

Cobalt Silicide Fabrication Using Protective Titanium

Assignee(s):

Mosel Vitelic, Inc.

Mountain View, California 22 September 2005

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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

In reviewing the file for the above patent application, Applicant's Attorney determined that the citation information for reference AK, a document entitled "Applied Materials Launches Advanced Cobalt Solution for Nano-Chip Manufacturing", in the Information Disclosure Statement submitted 25 March 2002 for this application was incomplete and partially wrong. Enclosed is a substitute PTO Form 1449 which lists this document with corrected citation information. Please use the corrected citation information in printing the patent that issues on the above application.

Hopwood, also listed on the accompanying substitute PTO Form 1449, was cited in the Response submitted 6 June 2005 to show that techniques for performing ionized physical vapor deposition include ionized sputtering and ionized evaporation.

Citation of the listed documents shall not be construed as:

1. an admission that the documents are necessarily prior art with respect to the instant invention;

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- 2. a representation that a search has been made; or
- 3. an admission that the information cited herein is, or is considered to be, material to patentability as defined in 37 CFR 1.56(b).

Please place this paper and the enclosures in the PTO file for the above application.

Please telephone Applicants' Attorney at 650-964-9767 if there are any questions.

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Respectfully submitted,

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Sheet 1 of 1 U.S. Department of Commerce, Patent and Trademark Office Atty Docket No. Application No. M-12524 US 10/056,154 MATION DISCLESURE STATEMENT BY APPLICANT Applicant(s) Confirmation No. Substitute Form Fortin, Vincent 2279 Filing Date Group 23 January 2002 2823 U.S. Patent Documents Document Filing Date If Initial Number Date Name Class Subclass Appropriate AA ABAC ADΑE ΑF AG AH ΑI AJ ΑK AL Foreign Patent Documents Translation Document Class Subclass Yes Date Country No AM AN AO AP AQ OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) Hopwood, "Ionized physical vapor deposition of integrated circuit interconnects", Physics of Plasmas, AR May 1998, pp. 1624 - 1631

AR Hopwood, "Ionized physical vapor deposition of integrated circuit interconnects", Physics of Plasmas, May 1998, pp. 1624 - 1631

AS "Applied Materials Launches Advanced Cobalt Solution for Nano-Chip Manufacturing", Business Wire, Applied Materials, http://www.businesswire.com/cgi-bin/cnn-storydisplay.cgi?story=www/between/webboc/bw.1204...1, Dec. 4, 2001, 1 page

AT

Examiner Date Considered

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.